



SHEET 1 OF 1

INFORMATION DISCLOSURE
CITATION IN AN
APPLICATION

(PTO-1449)

ATTY. DOCKET NO.
055071-0351SERIAL NO.
10/813,626APPLICANT
Robert SOCHAFILING DATE
March 31, 2004GROUP
4750 2851

U.S. PATENT DOCUMENTS

EXAMINER'S INITIALS	CITE NO.	Document Number Number-Kind Code ² (if known)	Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear
MB ↓		US 5,680,588	10-21-1997	Gortych et al.	
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		JP 2000-232657A				X

OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)

EXAMINER'S INITIALS	CITE NO.	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.
		BURN J. LIN, "The Exposure-Defocus Forest," Jpn. J. Appl. Phys. Vol. 33 (1994), pp. 6758-6764
		M. DUSA et al., "Study of mask aerial images to predict CD proximity and line and shortening of resist patterns," Proc. of SPIE Vol. 4349 (2001), pp. 148-159
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1 Applicant's unique citation designation number (optional). 2 Applicant is to place a check mark here if English language Translation is attached.



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<i>mt</i>		WO 98/40791	09/17/1998	Konin Klijke Philips Electronics N.V.		Yes	No

OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)

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